

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Gary Chen et al.
App. No.	:	Unknown
Filed	:	Herewith
For	:	SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED OXYNITRIDE DEFECTS PROTRUDING THEREFROM
Examiner	:	Unknown
Group Art Unit	:	Unknown

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing thirty-two (32) references. All of these references are of record in U.S. Patent Application Number 10/234,577, filed August 30, 2002 ("the prior application"). Since these references are of record in the prior application, copies are not being submitted herewith. This Information Disclosure Statement is being filed within three months of the filing date of this application or upon filing if this is a CPA or RCE, and no fee is required in accordance with 37 C.F.R. § 1.97(b)(1), (b)(2), or (b)(4).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 7/3/03

By: John R. King

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FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. MICRON.109DC1D1	APPLICATION NO. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Gary Chen et al.	
		FILING DATE Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	1	3,968,565	07/13/76	Bertens et al.			
	2	4,528,066	07/09/85	Merkling, Jr., et al.			
	3	4,554,050	11/19/85	Minford, et al.			
	4	4,671,852	06/9/87	Pyke			
	5	4,787,958	11/29/88	Lytle			
	6	4,900,690	02/13/90	Tamura			
	7	5,023,201	06/11/91	Stanasolovich et al.			
	8	5,100,826	03/31/92	Dennison			
	9	5,198,384	03/30/93	Dennison			
	10	5,202,287	04/13/93	Joshi et al.			
	11	5,425,392	06/20/95	Thakur, et al.			
	12	5,462,638	10/31/95	Datta, et al.			
	13	5,498,293	03/12/96	Ilardi et al.			
	14	5,712,168	01/27/98	Schmidt, et al.			
	15	5,798,296	08/26/98	Fazan, et al.			
	16	5,800,726	09/01/98	Cotte, et al.			
	17	5,801,425	09/01/98	Kuroi et al.			
	18	5,814,560	09/29/98	Cheung et al.			
	19	5,830,798	11/03/98	Dennison, et al.			
	20	5,888,894	03/30/99	Kong, et al.			
	21	5,907,791	05/25/99	Cappuzzo et al.			
	22	5,989,354	11/23/99	Dormer et al.			
	23	5,960,303	09/28/99	Hill			
	24	6,010,965	01/04/00	Shields			
	25	6,015,505	01/18/00	David et al.			
	26	6,136,211	10/24/00	Qian et al.			

EXAMINER	DATE CONSIDERED
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	

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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	27	6,221,746	04/24/01	Huang et al.			
	28	6,417,572	07/09/02	Chidambarrao et al.			

FOREIGN PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
							YES NO
	29	0 560 324 A1	09/15/93	Europe			

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
	30	<i>Silicon Processing for the VLSI Era - Volume 1: Process Technology</i> , Stanley Wolf and Richard N. Tauber, <u>Lattice Press</u> , Sunset Beach, California
	31	US Publication No. US 2001/0003062 A1, Inventor: Rebecca Y. Tang, Pub. Date: June 7, 2001, Title: GATE SIDEWALL PASSIVATION TO PREVENT ABNORMAL TUNGSTEN POLYCID GROWTH
	32	US Publication No. US 2001/0019894 A1, Inventors: Peng et al., Pub Date: September 6, 2001, Title: PRE-HEAT STEP (OR CHAMBER) IMPLEMENTED IN PR DRY ASH MACHINES TO EFFECTIVELY ELIMINATE PR EXTRUSION (BUBBLE) AFTER ALLOY

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